Claims 1-24 (canceled)

- 25. (previously presented)A coating for a substrate comprising a transparent Si₃N₄ or SiN_x layer applied directly on the substrate, a semimetallic layer above the Si₃N₄ or SiN_x layer, a further Si₃N₄ or SiN_x layer, and a dielectric oxide layer selected from the group consisting of Al₂O₃, SnO, Nb₂O₅, TiO₂ and SiO₂, wherein the dielectric oxide layer is disposed on the semimetallic layer, and the further Si₃N₄ layer is disposed on the dielectric oxide layer.
- 26. (previously presented) The coating for a substrate as claimed in claim 25, wherein the semimetallic layer comprises a CrN layer.
- 27. (previously presented) The coating for a substrate as claimed in claim 25, wherein a dielectric oxide layer is provided between the transparent Si_3N_4 or SiN_x layer and the semimetallic layer.
- 28. (previously presented) The coating for a substrate as claimed in claim 25, wherein x is a number smaller than 4/3.
- 29. (previously presented) The coating for a substrate as claimed in claim 26, wherein the semimetallic layer comprises NiCrN or NiCrO_x.
- 30. (previously presented)A coating for a substrate as claimed in claim 25, wherein the transparent Si₃N₄ or substoichiometric SiN_x layers have each a layer thickness of 20 to 120 nm.

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- 31. (previously presented) A coating for a substrate as claimed in claim 25, wherein the dielectric oxide layers have each a layer thickness of 4 to 120 nm.
- 32. (previously presented) A coating for a substrate as claimed in claim 25, wherein the semimetallic NiCrN, CrN or NiCrO_x layers have a layer thickness of 5 to 40 nm.
- 33. (previously presented)A coating for a substrate as claimed in claim 25, wherein said substrate is glass.
- 34. (previously presented)A coating for a substrate as claimed in claim 25, wherein said substrate is a synthetic material.
- 35. (previously presented)A coating for a substrate as claimed in claim 25, further comprising additional layers comprising Cr, Ni or NiCr.

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